

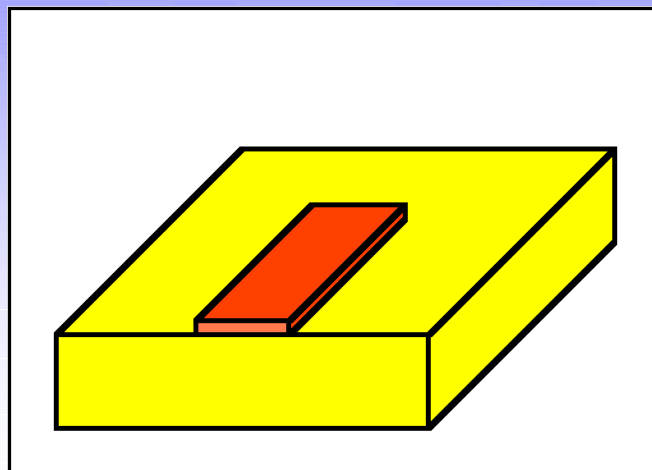
# Microlithographie

- Principe
- Mise en oeuvre
- Masques

[andre.stauffer@epfl.ch](mailto:andre.stauffer@epfl.ch)

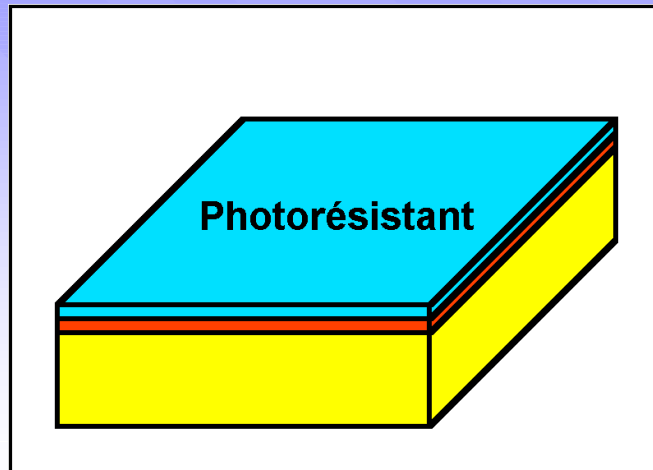
## Principe

Motif créé par microlithographie



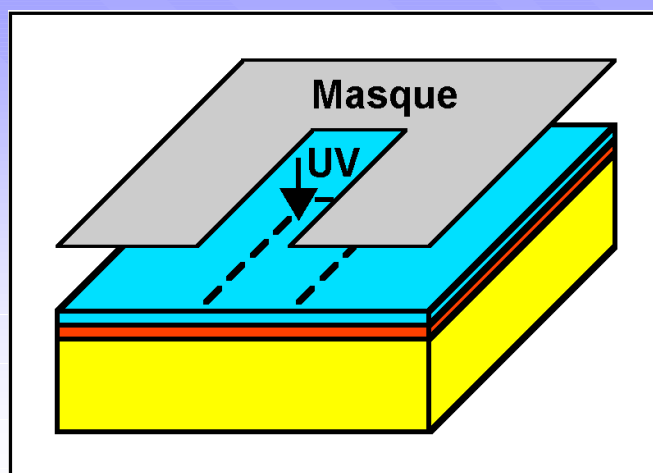
## Principe

### Dépôt du photorésistant



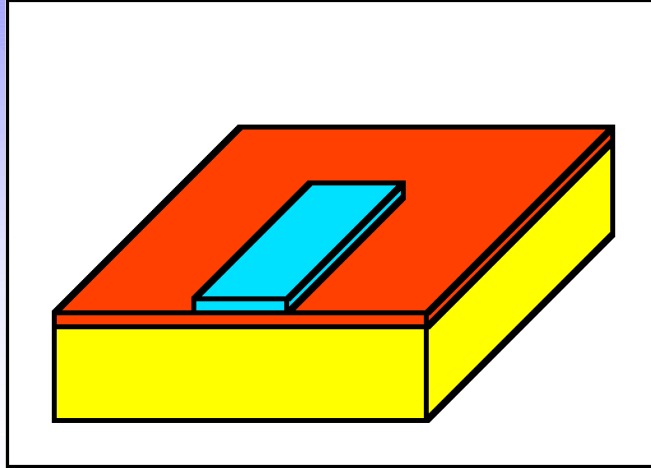
## Principe

### Exposition aux UV



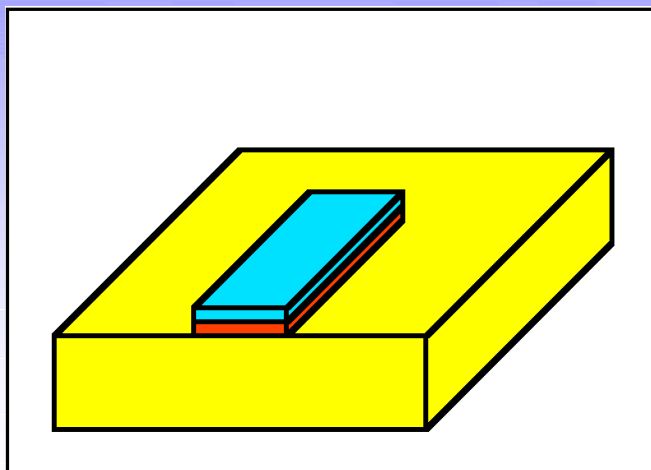
## Principe

Développement du photorésistant



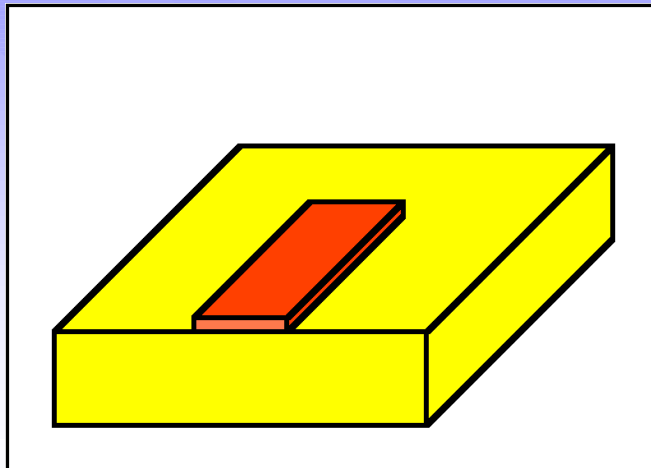
## Principe

Attaque chimique



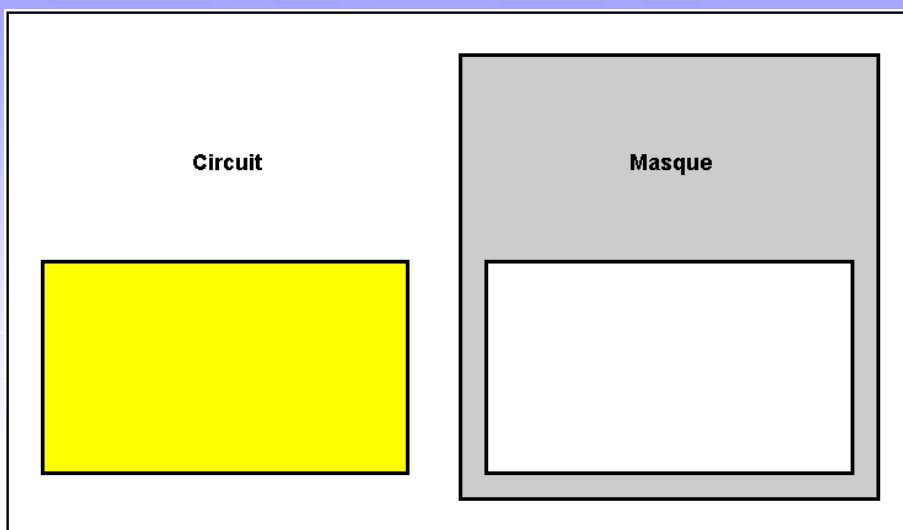
## Principe

Suppression du photo-résistant

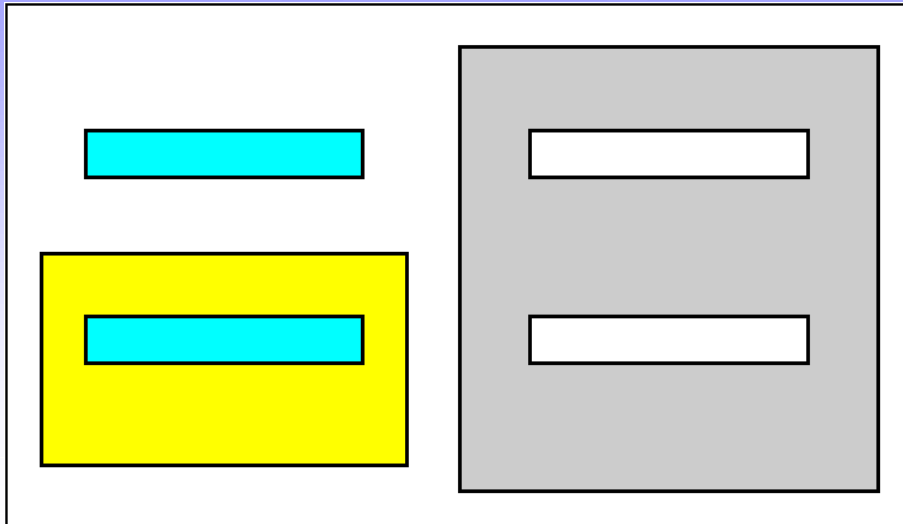


## Mise en oeuvre

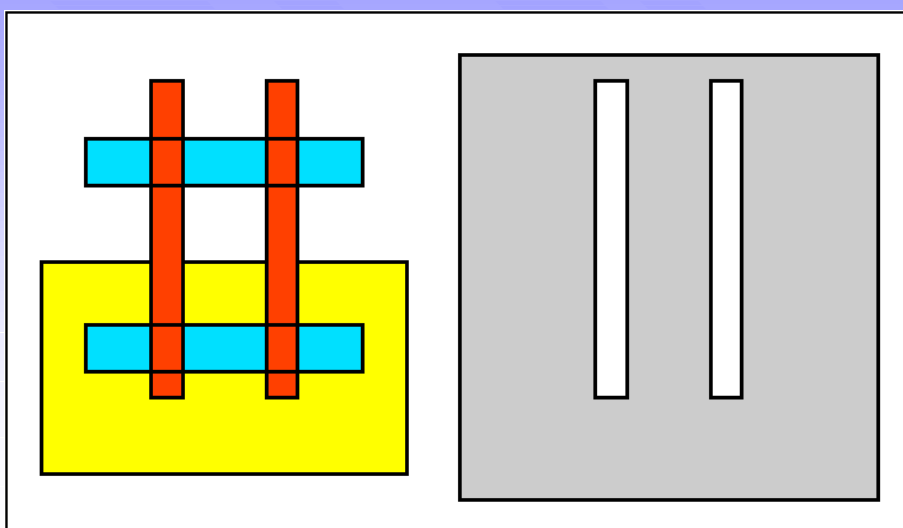
Création du caisson



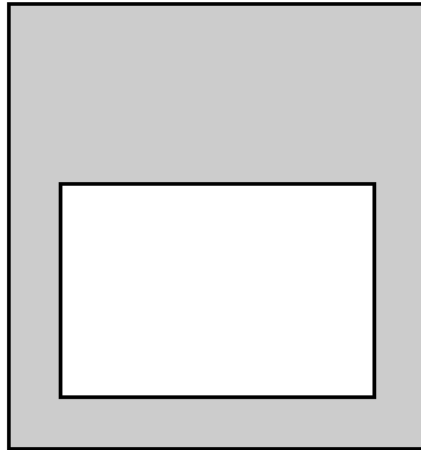
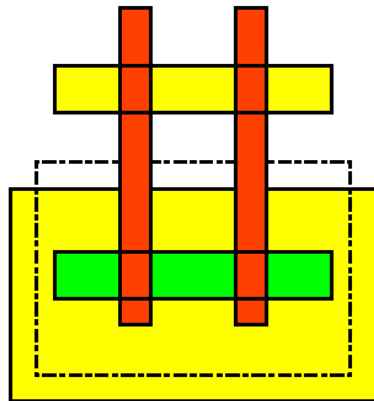
## Mise en oeuvre Dépôt d'oxyde



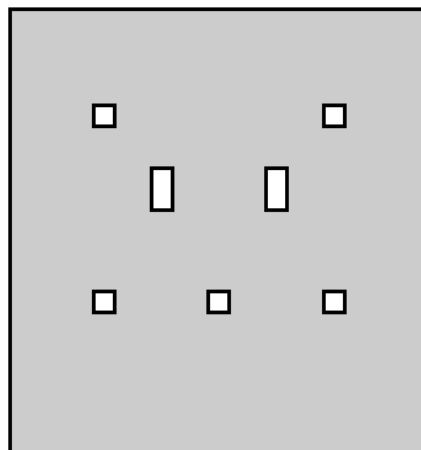
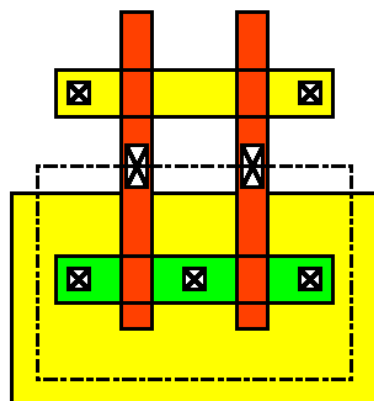
## Mise en oeuvre Dépôt de polysilicium



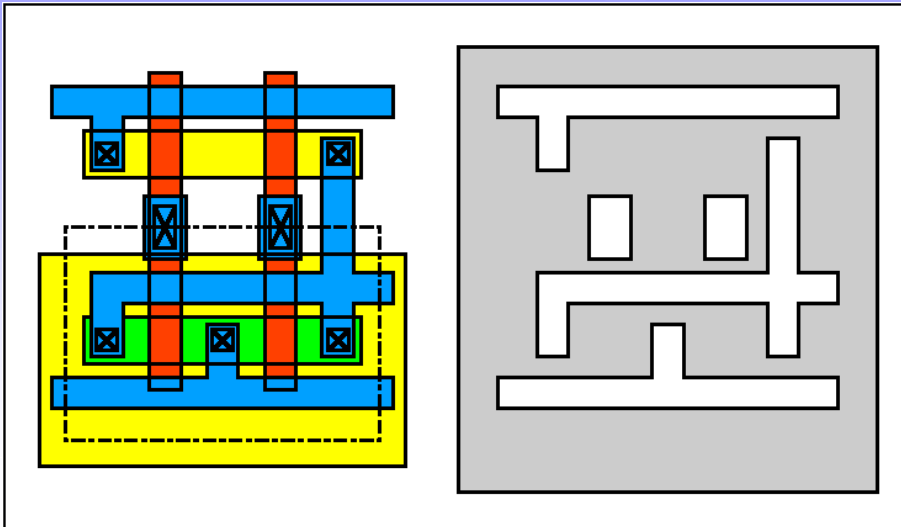
## Mise en oeuvre Dopage par implantation d'ions



## Mise en oeuvre Création des trous de contact



## Mise en oeuvre Dépôt de métal



## Mise en oeuvre Masques de la porte NOR

